

HUANG 5-8-5-2-2-25-3
A Mask Layer and Interconnect Structure for Dual Damascene Fabrication of a Semiconductor Device
Robert L. Wolter (407-926-7700)
Serial #10/026,257

1/15

FIG. 1
PRIOR ART

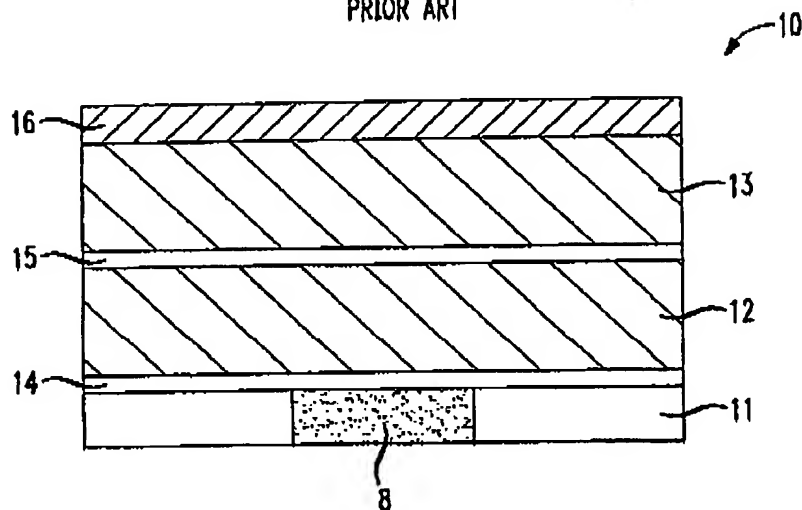
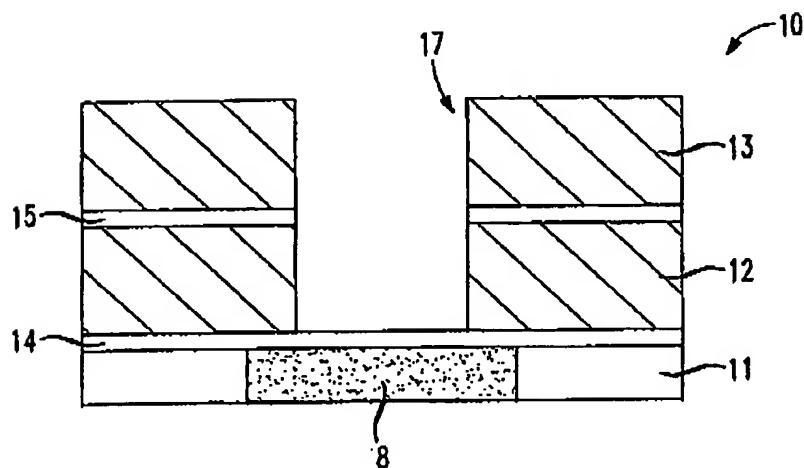


FIG. 2
PRIOR ART



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HUANG J-D-J-Z-Z-Z-J
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14/15

FIG. 27

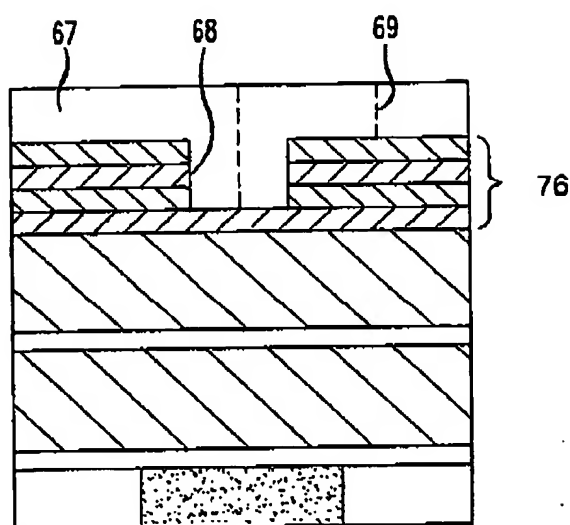
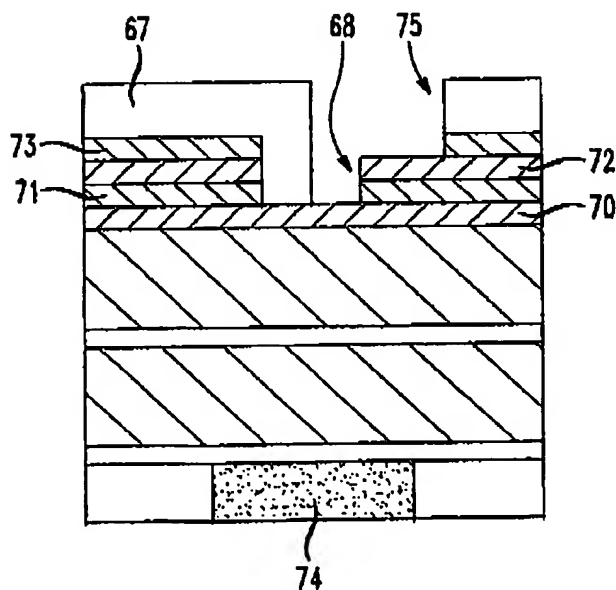


FIG. 28



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